

<b>Notice of References Cited</b>		Application/Control No.	Applicant(s)/Patent Under Reexamination BASCERI ET AL.	
		Examiner William M. Brewster	Art Unit 2823	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-			
	B	US-			
	C	US-			
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N	95/25340	09-1995	WO	Azuma et al.	HO1L 21/3205
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	P					
	Q					
	R					
	S					
	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Joo, "Fabrication and Characterization of MOCVD (Ba, Sr)TiO <sub>3</sub> Thin Films for High Density Capacitors", Proceeding of 1997 5th International Conference an VLSI and CAD", The Secretariat of ICVC '97, 1997.
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	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
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